

23672 EXPEDITED HANDLING BOX AF

IN THE U.S. PATENT AND TRADEMARK OFFICE

Inventor Bernd RECH et al
Patent App. 10/587,130
Filed 28 December 2007 Conf. No. 3123
For TRANSPARENT AND CONDUCTIVE OXIDE LAYER,
PRODUCTION AND....
Art Unit 1795 Examiner Berman, J
Hon. Commissioner of Patents
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FIFTH AMENDMENT - AFTER FINAL ACTION

This is in response to the Office Action mailed
03 September 2010.

The claims stand rejected on a combination of three new references, namely US 6,107,16 of Kariya, US 6,537,428 of Xiong, and US 2002/0190814 of Yamada.

Kariya uses sputtering to prepare ZnO from ceramic targets at high temperatures with low F doping (0.1-10t). This reference further mentions the possibility of reactive sputtering, but does not go into details on working points or lower deposition rate at high substrate temperature as observed by others (Szyszka